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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
09/467,168	12/20/1999	JAMES MARSHALL OATHOUT	SS2945	2005
	590 01/21/2004		EXAMINER	
E I DU PONT DE NEMOURS AND COMPANY LEGAL PATENT RECORDS CENTER			BEFUMO, JENNA LEIGH	
BARLEY MILL PLAZA 25/1128			ART UNIT	PAPER NUMBER
4417 LANCAS			1771	

DATE MAILED: 01/21/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

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		Application No.	Applicant(s)			
Office Action Summers		09/467,168	OATHOUT, JAMES MARSHALI	_		
	Office Action Summary	Examiner	Art Unit			
		Jenna-Leigh Befumo	1771			
Period for	The MAILING DATE of this communication app r Reply	ears on the cover sheet wit	h the correspondence address			
THE N - Extens after S - If the p - If NO - Failure - Any re	DRTENED STATUTORY PERIOD FOR REPL' MALLING DATE OF THIS COMMUNICATION. slons of time may be available under the provisions of 37 CFR 1. 31X (6) MONTHS from the mailing date of this communication, period for reply specified above is less than thirty (30) days, a reply period for reply is specified above, the maximum statutory period ve to reply within the set or extended period for reply will, by statute ply received by the Office later than three months after the mailing of patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a re	ply be timely filed (30) days will be considered timely.			
1)🖂	Responsive to communication(s) filed on 27 (October 2003 .				
2a)⊠	Ţhis action is FINAL . 2b) ☐ Th	is action is non-final.				
3) Disposition	Since this application is in condition for allowards closed in accordance with the practice under the or of Claims	ance except for formal matt Ex parte Quayle, 1935 C.D	ers, prosecution as to the merits is . 11, 453 O.G. 213.			
4)🛛 (Claim(s) 18-26 is/are pending in the applicatio	n.				
4	a) Of the above claim(s) is/are withdraw	vn from consideration.				
1	Claim(s) is/are allowed.					
6)🖂 (Claim(s) 18-26 is/are rejected.					
7) 🗆 (Claim(s) is/are objected to.					
i	Claim(s) are subject to restriction and/or	election requirement.				
Applicatio						
9)□ ⊤	he specification is objected to by the Examiner	:				
10)□ TI	he drawing(s) filed on is/are: a)□ accep	ted or b) objected to by the	e Examiner.			
	Applicant may not request that any objection to the	drawing(s) be held in abeyar	ice. See 37 CFR 1.85(a).			
11)[] TI	he proposed drawing correction filed on	is: a) ☐ approved b) ☐ dis	approved by the Examiner.			
	If approved, corrected drawings are required in rep		•			
12)∏ Ti	he oath or declaration is objected to by the Exa	aminer.				
Priority un	nder 35 U.S.C. §§ 119 and 120					
13) 🗌 🛭 A	Acknowledgment is made of a claim for foreign	priority under 35 U.S.C. §	119(a)-(d) or (f).			
a)	All b)☐ Some * c)☐ None of:					
1	. Certified copies of the priority documents	have been received.				
2	2. Certified copies of the priority documents have been received in Application No					
3	Copies of the certified copies of the priori application from the International Bur- te the attached detailed Office action for a list of	ty documents have been re	eceived in this National Stage			
	knowledgment is made of a claim for domestic					
a)[The translation of the foreign language prov	visional application has bee	en received.			
Attachment(s	knowledgment is made of a claim for domestic	priority under 35 U.S.C. §	§ 120 and/or 121.			
	of References Cited (PTO-892)	4 .□	(DTO 440) B			
2) Notice	of Draftsperson's Patent Drawing Review (PTO-948)		mmary (PTO-413) Paper No(s) prmal Patent Application (PTO-152)			
	ation Disclosure Statement(s) (PTO-1449) Paper No(s)	6) 🗌 Other:				
J.S. Patent and Trad PTOL-326 (Rev		ion Summary	Part of Paper No. 0104			

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DETAILED ACTION

1. The Applicant's response, filed October 27, 2003 has been received. Claims 18-26 are pending.

Claim Rejections - 35 USC § 103

- 2. The text of those sections of Title 35, U.S. Code not included in this action can be found in a prior Office action.
- 3. Claims 18 22, 24, and 26 stand rejected under 35 U.S.C. 103(a) as obvious over Bhattacharjee et al. (6,235,660) in view of Fujii (6,159,421) for the reasons of record.
- 4. Claim 25 stands rejected under 35 U.S.C. 103(a) as being unpatentable over

 Bhattacharjee et al. in view of Fujii as applied to claim 18 above, and further in view of Morin et al. (6,189,189) for the reasons of record.
- 5. Claim 23 stands rejected under 35 U.S.C. 103(a) as being unpatentable over Bhattacharjee et al. in view of Fujii as applied to claim 18 above, and further in view of Beaty et al. (5,807,870) for the reasons of record.

Response to Arguments

6. Applicant's arguments filed October 27, 2003 have been fully considered but they are not persuasive. The Applicant argues that there is no motivation to combine Bhattacharjee et al. with Fujii et al. to produce the claimed invention, i.e., a method of cleaning Class 10 cleanrooms with nonwoven wipers (Response, page 2). While Bhattacharjee et al. discloses that nonwoven fabrics can be used in cleanrooms for semiconductor fabrication plants, pharmaceutical facilities, and other applications where extreme cleanliness must be maintained, Bhattacharjee et al. fails to teach what levels of cleanrooms are used in these applications. Fujii et al. is relied on to teach

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that semiconductor are produced in cleanrooms having a Class 10 level (column 9, lines 27 – 30). In other words, Fujii et al. defines what cleanroom conditions are used in semiconductor fabrication. Therefore, since Fujii et al. discloses that semiconductors fabrications includes rooms having a Class 10 level and Bhattacharjee et al. teaches that nonwoven cleaning wipes can be used in cleanrooms for semiconductor fabrication plants, it would have been obvious to one of ordinary skill in the art to use nonwoven wipes in Class 10 cleanrooms which are used to produce semiconductors. Thus, there is motivation to combine the two references since Fujii et al. discloses specific details about cleanrooms in semiconductor fabrication plants, while Bhattacharjee et al. discusses using nonwoven wipes in semiconductor fabrication without teaching what cleanliness levels are used in semiconductor fabrication. Thus, the rejections is maintained.

Conclusion

7. **THIS ACTION IS MADE FINAL.** Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to Jenna-Leigh Befumo whose telephone number is (571) 272-1472. The examiner can normally be reached on Monday - Friday (8:00 - 5:30).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Terrel Morris can be reached on (571) 272-1478. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (571) 272-0994.

Jenna-Leigh Befumo January 9, 2004

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